




<b>Search Notes</b>  	Application/Control No.  10668974	Applicant(s)/Patent Under Reexamination  SHIMIZU ET AL.
	Examiner Jacob, Mary C	Art Unit 2123

Notes	Date	Examiner
Inventor Search: East, Google Scholar, IEEE, ACM	07/03/2006	MCJ
Assignee Name Search: East, Google Scholar	07/03/2006	MCJ
East Search: see search history	07/05/2006	MCJ
IEEE: transistor model, minitaurize, scale, characteristics, parameter, modify, correct, optimize, update, extract, threshold voltage, mobility shallow trench isolation, STI, isolation technology, simulation, characteristic, parameter, modify, correct, update, extract, optimize diffusion length, diffusion width, trench, simulation	07/05/2006	MCJ
IEEE, Google Scholar: Mobility model, mobility, correction factor	07/07/2006	MCJ
Talked to Paul Rodriguez, SPE AU2123 about claims 5, 6, 11, 12	7/7/06	MCJ
U.S. Patent and Trademark Office		Part of Paper No.:

<p><b>Searched</b></p> 	<p>Application/Control No.</p> <p>10668974</p>	<p>Applicant(s)/Patent Under Reexamination</p> <p>SHIMIZU ET AL.</p>
	<p>Examiner</p> <p>Jacob, Mary C</p>	<p>Art Unit</p> <p>2123</p>

Class	SubClass	Date	Examiner
703	14	07/05/2006	MCJ

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<b><i>Interference Searched</i></b>  	Application/Control No.  10668974	Applicant(s)/Patent Under Reexamination  SHIMIZU ET AL.
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